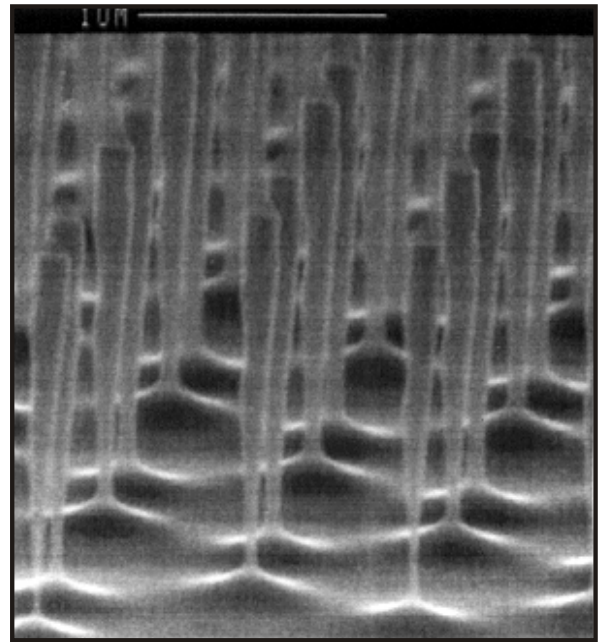


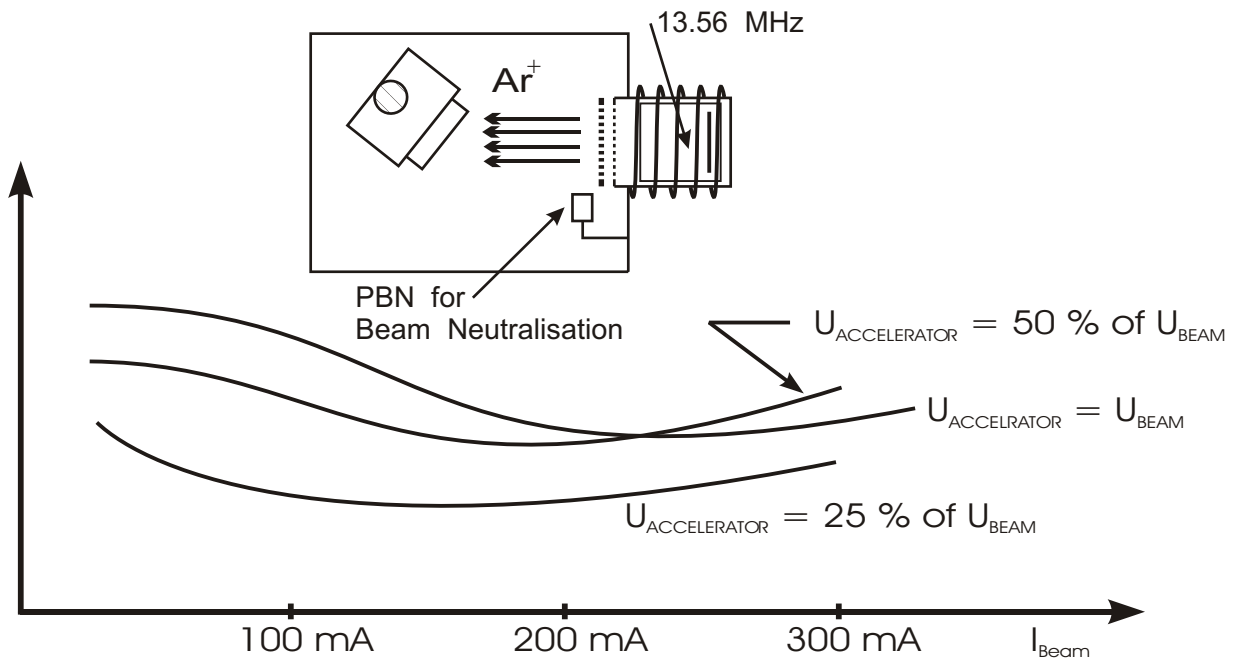
Ionfab Data

Microdivergence: GaAs Cl₂ - RIBE



Ionfab 300 Plus

10:1 Aspect Ratio GaAs Etch by Cl₂
(courtesy of Sandia, US)



Dependence of the (Micro- and Macro-) Divergence on Beam Energy and Current